What is claimed is:

1. A substrate processing method comprising the steps of:

(a) providing a substrate processing system including:

first processing units that number N each adapted to process a substrate by a first treatment with a first processing fluid, where N is a natural number not less than 3;

at least one second processing unit adapted to process the substrate; and

a supply device adapted to generate the first processing fluid to be supplied to the first processing units;

(b) processing one of the substrates including the steps of;

(i) loading said one of the substrates into one of the first processing units;

(ii) performing the first treatment by using the first processing fluid to said one of the substrates in said one of the first processing units;

(iii) transferring said one of the substrates, having been processed by said one of the first processing units, to the second processing unit; and

(iv) performing the second treatment to said one of the substrate by using the second processing unit; and

(c) repeating the step (b) plural times to process the substrates, while changing the first processing unit used in the steps (i) and (ii), with at least two of the first processing units simultaneously carrying out the step (ii);

wherein:

the supply device has a capacity of supplying the first processing fluid to only N-n of the first processing units simultaneously at respective supply rates each in accordance with a demand for appropriately performing the first process in each of the first processing units, where n is a natural number and N-n is not less than 2; and

in the step (c), timing of starting of the steps (i) is determined so as to avoid a case where more than N-n of the first processing units are simultaneously carrying out the steps (ii) each use the first processing fluid.

2. The method according to claim 1, wherein, when the step (b) is repeated, the steps (i) are carried out in the first processing units by turns at T/(N-n) intervals, where T is a time period necessary for carrying out the step (ii).

3. A substrate processing system comprising:

a plurality of first processing units that number N each adapted to process a substrate by a first treatment with a first processing fluid, where N is a natural number not less than 3;

at least one second processing unit adapted to process the substrate; and

a supply device adapted to generate the first processing fluid to be supplied to the first processing units, the supply device having a capacity of supplying the first processing fluid to only N-n of the first processing units simultaneously at respective supply rates each complies with a demand for appropriately performing the first process in each of the first processing units, where n is a natural number and N-n is not less than 2; and

a substrate conveyer adapted to convey the substrate and to load and unload the substrate into and from the first and second processing units; and

a controller that controls a timing of loading of the substrate into the first processing units by the substrate conveyer so as to avoid a case where more than N-n of the first processing units are simultaneously carrying out the first treatment each using the first processing fluid, where n is a natural number and N-n is not less than 2.

4. The system according to claim 3, wherein the controller is configured to control the substrate conveyer so that the conveyer loads the substrates into the first processing units by turns at T/(N-n) intervals, where T is a time period necessary for carrying out the first treatment in each of the first processing units by using the first processing fluid.